

AMENDMENTS TO THE CLAIMS

1-3. (Cancelled)

4. (Currently Amended) A method of etching and cleaning objects contained in a vessel, comprising the steps of:

introducing an etching solution ~~to a lower portion of a~~into the vessel ~~containing objects to be cleaned~~ from below the objects;

etching the objects with the etching solution;

introducing a pressurized gas ~~to an upper portion of~~into the vessel from above the objects to force the etching solution out ~~through the lower portion of~~ the vessel from below the objects;

cleaning the objects by introducing a cleaning solution into the ~~lower portion of the vessel~~ from below the objects; and

draining the cleaning solution from the ~~upper portion of the vessel~~ from above the objects.

5. (Previously Presented) The method of claim 4, wherein the sequential steps of forcing out the etching solution alone and draining the cleaning solution are carried out through different draining pipes connected to the vessel.

6. (Original) The method of claim 4, wherein the pressurized gas is nitrogen gas.

7. (Original) The method of claim 4, wherein the etching solution is Oxalic acid solution or diluted Oxalic acid solution.

8. (Original) The method of claim 4, wherein the cleaning solution is deionized water.

9. (Previously Presented) The method of claim 4, wherein the step of forcing out the etching solution is enhanced by pumping the etching solution out of the vessel.

10. (Previously Presented) The method of claim 4, further comprising:
drying the objects by providing drying gas into the vessel after draining the cleaning solution.

11. (Previously Presented) The method of claim 10, wherein the drying gas includes isopropyl alcohol.